Supporting Information for

# Air-Stable Ultrabright Inverted Organic Light-Emitting

## **Devices with Metal Ion-Chelated Polymer Injection Layer**

Shihao Liu<sup>1, 2, #</sup>, Chunxiu Zang<sup>1, #</sup>, Jiaming Zhang<sup>1</sup>, Shuang Tian<sup>2</sup>, Yan Wu<sup>2</sup>, Dong Shen<sup>2</sup>, Letian Zhang<sup>1</sup>, Wenfa Xie<sup>1, \*</sup>, Chun-Sing Lee<sup>2, \*</sup>

<sup>1</sup>State Key Laboratory of Integrated Optoelectronics, College of Electronics Science and Engineering, Jilin University, 2699 Qianjin Street, Changchun 130012, P. R. China

<sup>2</sup>Center of Super-Diamond and Advanced Films (COSDAF), Department of Chemistry, City University of Hong Kong, Kowloon, Hong Kong, P. R. China

<sup>#</sup>S.H. Liu and C.X. Zang have contributed equally to this work.

\*Corresponding authors. E-mail: <u>xiewf@jlu.edu.cn</u> (Wenfa Xie), <u>apcslee@cityu.edu.hk</u> (Chun-Sing Lee)

## **Supplementary Figures and Table**



Fig. S1 Molecular structures of the used small molecular materials in the inverted OLEDs

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Fig. S2 A photograph of the synthesized PEI-Zn powder



Fig. S3 (a) Current density-voltage-brightness and (b) EQE-brightness characteristics of device with PEI interlayer after adding zinc acetate dihydrate with different concentrations



Fig. S4 N 1s XPS spectra of the PEI and the PEI-Zn layers coated on ITO

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Fig. S5 FTIR spectra of the PEI and the PEI-Zn



Fig. S6 Electrochemical stability of the PEI and the PEI-Zn films





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Fig. S8 UPS spectra of the PEI-Zn and the PEI coated on the ITO



Fig. S9 Tauc plots of the PEI-Zn and the PEI



**Fig. S10** (**a**) Current density-voltage-brightness, (**b**) current efficiency-brightnesspower efficiency, (**c**) EQE-brightness and (d) optical power dissipation characteristics of device PEI-Zn and device ZnO/PEI. The structure of device Zn/PEI is ITO/ZnO (30 nm)/PEI (15 nm)/ DMAC-BPP (10 nm)/CBP: 10wt% Ir(ppy)<sub>3</sub> (20 nm)/TCTA (5 nm)/TAPC (35 nm)/MoO<sub>3</sub> (3 nm)/Ag (120 nm)



Fig. S11 Atom force microscope (AFM) images of PEI and PEI-Zn films



**Fig. S12** (**a**) Resistance-voltage characteristic of a conventional OLED with a structure of ITO/MoO<sub>3</sub> (3 nm)/TAPC (30 nm)/TCTA (5 nm)/CBP: 10 wt% Ir(ppy)<sub>3</sub> (30 nm)/TmPyPB (50 nm)/LiF/Mg: 10 wt% Ag (120 nm). (**b**) Resistance-voltage characteristics of PEI-based and PEI-Zn-based single carrier devices with a structure of ITO/PEI or PEI-Zn/DMAC-BP (50 nm)/Mg: 10 wt% Ag (120 nm)



**Fig. S13** (a) Energy levels of the PEI or the PEI-Zn used for the simulation of hole accumulations. (b) Simulated hole density of device PEI and device PEI-Zn. The energy levels of the PEI and PEI-Zn is calculated by following the method of Zhou et al (see Fig. S2 of ref. 22). The electron affinity is given by the equation of  $E_{\rm F}$ +0.5\* $E_{\rm g}$ , and the ionization potential energy is provided by the equation of  $E_{\rm F}$ -0.5\* $E_{\rm g}$ . The values of  $E_{\rm F}$  and  $E_{\rm g}$  are extracted from the Tauc plots (Figure S9) and the UPS spectra (Figure S8). The brown green rectangle and violet circle respectively represent the hole accumulation at the EML/TPBi interface and the DMAC-BPP/EJL interface. The simulation is conducted by the commercial simulation software SimOLED.

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**Fig. S14** Current density-voltage characteristics of (**a**) PEI-based devices and (**b**) PEI-Zn-based devices with an orange probe at different distance from the TPBi/EML interface



**Fig. S15** Transient PL decay characteristics (@520 nm) of the CBP:10 wt% Ir(ppy)<sub>3</sub> films (20 nm) on the PEI/DMAC-BP/TPBi and the PEI-Zn/DMAC-BP/TPBI substrates

Material	Mobilities (cm <sup>2</sup> V <sup>-1</sup> S <sup>-1</sup> )		Energy Level (eV)		Relative dielectric	Thickness
	Electron	Hole	LUMO	НОМО	constants	(1111)
ΙΤΟ	WF=-4.5				3.2	120
PEI	10-8	10-8	-1.2	-6.4	3.0	15
PEI-Zn	10-5	10-5	-2.1	-5.7	3.0	15
DMAC- BPP	8.5×10 <sup>-5</sup>	1.9×10 <sup>-5</sup>	-2.5	-5.4	3.0	10
TPBI	3.3×10 <sup>-5</sup>	10-6	-2.6	-6.2	3.0	5
CBP	3×10 <sup>-4</sup>	10-3	-2.6	-5.9	3.0	20
Ir(ppy) <sub>3</sub>	10-6	2.9×10 <sup>-5</sup>	-3.0	5.6	3.0	20, 10 wt%
ТСТА	10 <sup>-8</sup>	3×10-4	-2.2	-5.6	3.0	5
TAPC	10 <sup>-6</sup>	10-2	-1.8	-5.3	3.0	35
Ag	WF=-5.3				-10.991+0.33i	100

Table S1 Parameters for simulation of hole density